

	Hits	Search Text	DBs
25	30	(mask or microstructure or photosensitive or photoresist or resist or (e\$2beam near9 resist)) and (((direct near9 writ\$4) or (pass\$3 near9 offset) or passes) same (gray near9 scale near9 pattern\$4)) and develop\$4	US-PGPUB; USPAT
26	15	(mask or microstructure or photosensitive or photoresist or resist or (e\$2beam near9 resist)) and (((direct near9 writ\$4) or (pass\$3 near9 offset) or passes) same (gray near9 scale near9 pattern\$4)) and develop\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB
27	87	(mask or microstructure or photosensitive or photoresist or resist or (e\$2beam near9 resist)) and (((direct near9 writ\$4) or (pass\$3 near9 offset) or (multiple near9 (expos\$4 or sweep)) or pass\$2) same (resist or photoresist or photosensitive or cur\$3)) and ((writ\$4 or form\$4 or mak\$3 or produc\$3 or manufactur\$3) same (gray near9 scale near9 pattern\$4)) and develop\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	36	<pre>((direct near9 writ\$4) or (pass\$3 near9 offset) or (single near9 (expos\$4 or sweep)) or pass\$2) same (resist or photoresist or photosensitive)) and ((writ\$4 or form\$4 or mak\$3 or produc\$3 or manufactur\$3) same (gray near9 scale near9 pattern\$4)) and develop\$4 and (e\$2beam or UV or laser or IR or X\$2ray) and (heat\$4 or bak\$4 or (post near9 bak\$4))</pre>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB